

|    | Hits | Search Text   | DBs   |
|----|------|---|---|
| 34 | 1    | ((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid) near6 gap))) and ((substrate or wafer) same (rotation or rotational or rotating) same (dry\$4 or remov\$4) same alcohol) and ((integrat\$3 near5 circuit\$3) or (circuit\$4 near4 device))) | US-PGPUB;<br>USPAT; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB |
| 35 | 1    | ((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid) near6 gap))) and ((substrate or wafer) same (rotation or rotational or rotating) same (dry\$4 or remov\$4) same alcohol) and ((integrat\$3 near5 circuit\$3) or (circuit\$4 near4 device))) | US-PGPUB  |

|    | Hits | Search Text   | DBs   |
|----|------|---|---|
| 36 | 1    | ((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid) near6 gap))) and ((substrate or wafer) same (reduc\$3 or decreas\$4 or eliminat\$4) same (non\$3uniformi\$4 or unifor\$5) same (CD or (critical near4 dimension)) same (dry\$4 or remov\$4) same (fluid or liquid)) | US-PGPUB;<br>USPAT; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB |
| 37 | 1    | ((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid) near6 gap))) and ((substrate or wafer) same (reduc\$3 or decreas\$4 or eliminat\$4) same (non\$3uniformi\$4 or unifor\$5) same (CD or (critical near4 dimension)) same (dry\$4 or remov\$4) same (fluid or liquid)) | US-PGPUB  |